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R 00 P 1582

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BY: James P. [signature] DATE: 6/14/01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor : Klaus Lowack et al.
Appl. No. : 09/817,967
Filed : March 27, 2001
Title : Component having at least two mutually adjacent insulating layers and corresponding production method

P R E L I M I N A R Y A M E N D M E N T

Hon. Commissioner of Patents and Trademarks,
Washington, D. C. 20231

S i r :

Preliminary to examination, kindly amend the above-identified application as follows:

In the Specification:

Page 1, between lines 4 and 6, insert

-- Background of the Invention:

Field of the Invention: --

Page 2, between lines 3 and 5, insert

-- Summary of the Invention: --

Page 10, between lines 18 and 20, insert

-- Description of the Preferred Embodiments: --

Page 20, top, replace "Abstract" with

-- Abstract of the Disclosure: --

Page 20, lines 3-4, delete the paragraph reading, "Component having at least two adjacent insulating layers and production process therefore".

In the Claims:

Cancel claims 1- 10 and enter the following new claims.

-- 11. A component, which comprises:

a substrate;

a lower insulating layer having a layer thickness between 0.05 μm and 50 μm and having a region;

at least one upper insulating layer having a layer thickness between 0.05 μm and 50 μm and having a region; and

at least one activated region that is activated for a process selected from the group consisting of subsequent metallization, photosensitization, hydrophobicization and surface functionalization that is other than metallization, photosensitization, and hydrophobicization;

said at least one activated region being selected from the group consisting of said region of said lower insulating layer and said region of said at least one upper insulating layer;

said lower insulation layer located adjacent said at least one upper insulation layer.

12. The component according to claim 11, wherein said substrate, said lower insulating layer, and said at least one upper insulating layer form a component selected from the group consisting of an electronic component and a microelectronic component.

13. The component according to claim 11, wherein said lower insulating layer is chemically different from said at least one upper insulating layer.

14. The component according to claim 11, wherein said at least one said upper layer is a layer selected from the group consisting of a patterned layer and a mask layer for activating said lower layer.

15. The component according to claim 11, wherein said at least one activated region is a region selected from the group consisting of a seeded region and a metallized region.

16. A process for producing a component, which comprises:

in a first working step, applying a lower insulating layer to a substrate;

in a second working step, activating at least one region of the lower insulating layer; and

in a third working step, applying at least one upper insulating layer to the lower, activated insulating layer and patterning the at least one upper insulating layer.

17. The process according to claim 16, which comprises patterning the lower insulating layer in the first working step.

18. The process according to claim 16, which comprises choosing a selected layer from the group consisting of the at least upper one insulating layer and the lower insulating layer and patterning the selected layer after the selected layer has been applied.

19. A process for producing a component, which comprises:

in a first working step, applying a first insulating layer to a substrate;

in a second working step, applying a second insulating layer and patterning the second insulating layer; and

in a third working step, activating a layer selected from the group consisting of the first insulating layer and the second insulating layer.

20. The process according to claim 19, which comprises patterning the first insulating layer in the first working step.

21. The process according to claim 19, which comprises patterning the second insulating layer after the second working step and before the third working step.

22. The process according to claim 21, which comprises patterning the lower insulating layer, after the first working step.

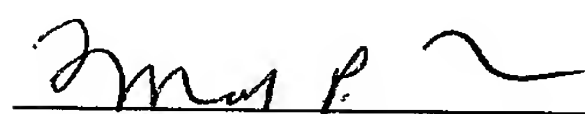
23. The process according to claim 19, which comprises patterning the lower insulating layer, after the first working step. --

Remarks:

The preliminary amendment is being filed in an effort to correct informalities and to provide improved translations of certain wording in the initial application. The changes neither narrow nor broaden the claims and are not provided for any statutory reason related to patentability. The recommended subheadings have been inserted at the proper locations in the text. All of the changes are properly supported in the original application. No new matter has been added.

An early action on the merits of the application is solicited.

Respectfully submitted,



For Applicants

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MPW:kc

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VERSION WITH MARKINGS TO SHOW CHANGES MADE

Page 20, top, [Abstract] Abstract of the Disclosure:

Page 20, lines 3-4, [Component having at least two adjacent
insulating layers and production process therefore]